



Session Title:	[WeF2] Nano Thin Film Deposition IV
Session Date:	November 13 (Wed.), 2024
Session Time:	14:10-15:55
Session Room:	Room F (Ballroom, 5F, Grand Josun Busan)
Session Chair:	Dr. Mihaela Popovici (imec, Belgium)

[WeF2-1] [Invited]

14:10-14:40

Nano Thin Film Technologies for Charge Trap Flash in VNAND

HanMei Choi, Bio Kim, HyungJoon Kim, Kwangmin Park, Philouk Nam, Kyong-Won An, DongHun Sin, Guk-Hyon Yon, Jaehyun Yang, Dongsung Choi, Sangsoo Lee, Sookyem Yong, Heedon Hwang, JongMyeong Lee (Samsung Electronics Co., Korea)

[WeF2-2] [Invited]

14:40-15:05

SMART Nanometallization for Energy-Efficient and Reliable Edges

Hanwool Yeon (GIST, Korea)

[WeF2-3] [Invited]

15:05-15:30

Recent Advances in Mo-Based Electrode Materials for High-Performance DRAM Cell Capacitors

Jeong Hwan Han (Seoul Nat'l Univ. of Science and Tech., Korea)

[WeF2-4] [Invited]

15:30-15:55

Advanced ALD Process for Meta-Stable Phased Thin Film Deposition

Woojin Jeon (Kyung Hee Univ., Korea)